

| L Number | Hits | Search Text  | DB  | Time stamp       |
|----------|------|--|---|------------------|
| -        | 21   | US-3223040-\$.DID. OR US-4793524-\$.DID. OR US-5095938-\$.DID. OR US-5098741-\$.DID. OR US-5195655-\$.DID. OR US-5273851-\$.DID. OR US-5314724-\$.DID. OR US-5356034-\$.DID. OR US-5494712-\$.DID. OR US-5534069-\$.DID. OR US-5593741-\$.DID.   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 16:03 |
| -        | 27   | US-3223040-\$.DID. OR US-4793524-\$.DID. OR US-5095938-\$.DID. OR US-5098741-\$.DID. OR US-5195655-\$.DID. OR US-5273851-\$.DID. OR US-5314724-\$.DID. OR US-5356034-\$.DID. OR US-5494712-\$.DID. OR US-5534069-\$.DID. OR US-5593741-\$.DID.) (US-4894254-\$.DID. OR US-4822632-\$.DID. OR US-4096315-\$.DID.  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/01 11:45 |
| -        | 2    | 6028015.pn.  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/01 11:57 |
| -        | 37   | (US-3223040-\$.DID. OR US-4793524-\$.DID. OR US-5095938-\$.DID. OR US-5098741-\$.DID. OR US-5195655-\$.DID. OR US-5273851-\$.DID. OR US-5314724-\$.DID. OR US-5356034-\$.DID. OR US-5494712-\$.DID. OR US-5534069-\$.DID. OR US-5593741-\$.DID.) (US-4894254-\$.DID. OR US-4822632-\$.DID. OR US-4096315-\$.DID.) 6028015.pn. (US-5876503-\$.DID. OR US-5620524-\$.DID. OR US-5641559-\$.DID. OR US-5738804-\$.DID.) | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/01 11:57 |
| -        | 8    | US-5876503-\$.DID. OR US-5620524-\$.DID. OR US-5641559-\$.DID. OR US-5730804-\$.DID.   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 16:20 |
| -        | 37   | (US-3223040-\$.DID. OR US-4793524-\$.DID. OR US-5095938-\$.DID. OR US-5098741-\$.DID. OR US-5195655-\$.DID. OR US-5273851-\$.DID. OR US-5314724-\$.DID. OR US-5356034-\$.DID. OR US-5494712-\$.DID. OR US-5534069-\$.DID. OR US-5593741-\$.DID.) (US-4894254-\$.DID. OR US-4822632-\$.DID. OR US-4096315-\$.DID.) 6028015.pn. (US-5876503-\$.DID. OR US-5620524-\$.DID. OR US-5641559-\$.DID. OR US-5730804-\$.DID.) | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 16:25 |
| -        | 6    | "2280169"  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 16:04 |
| -        | 8    | "2220869"  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 16:08 |
| -        | 7    | "2111064"  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 16:08 |
| -        | 13   | "2108133"  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 16:10 |
| -        | 11   | "529334"   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 16:10 |

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|---|----|--|---|------------------|
| - | 5  | "9808249"  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 16:18 |
| - | 17 | "9401885"  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 16:18 |
| - | 2  | "5270267".pn.  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 16:21 |
| - | 18 | "19654737"   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 16:23 |
| - | 37 | (US-3223040-\$.DID. OR US-4793524-\$.DID. OR US-5095938-\$.DID. OR US-5098741-\$.DID. OR US-5195655-\$.DID. OR US-5273851-\$.DID. OR US-5314724-\$.DID. OR US-5356034-\$.DID. OR US-5494712-\$.DID. OR US-5534069-\$.DID. OR US-5593741-\$.DID.) (US-4894254-\$.DID. OR US-4822632-\$.DID. OR US-4096315-\$.DID.) 6028015.pn. (US-5876503-\$.DID. OR US-5620524-\$.DID. OR US-5641559-\$.DID. OR US-5730804-\$.DID.)                                 | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 16:26 |
| - | 39 | "5270267".pn. ((US-3223040-\$.DID. OR US-4793524-\$.DID. OR US-5095938-\$.DID. OR US-5098741-\$.DID. OR US-5195655-\$.DID. OR US-5273851-\$.DID. OR US-5314724-\$.DID. OR US-5356034-\$.DID. OR US-5494712-\$.DID. OR US-5534069-\$.DID. OR US-5593741-\$.DID.) (US-4894254-\$.DID. OR US-4822632-\$.DID. OR US-4096315-\$.DID.) 6028015.pn. (US-5876503-\$.DID. OR US-5620524-\$.DID. OR US-5641559-\$.DID. OR US-5730804-\$.DID.) )                | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 16:27 |
| - | 2  | 5786039.pn.  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 16:28 |
| - | 41 | ("5270267".pn. ((US-3223040-\$.DID. OR US-4793524-\$.DID. OR US-5095938-\$.DID. OR US-5098741-\$.DID. OR US-5195655-\$.DID. OR US-5273851-\$.DID. OR US-5314724-\$.DID. OR US-5356034-\$.DID. OR US-5494712-\$.DID. OR US-5534069-\$.DID. OR US-5593741-\$.DID.) (US-4894254-\$.DID. OR US-4822632-\$.DID. OR US-4096315-\$.DID.) 6028015.pn. (US-5876503-\$.DID. OR US-5620524-\$.DID. OR US-5641559-\$.DID. OR US-5730804-\$.DID.) ) ) 5786039.pn. | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 10:14 |
| - | 14 | "254205"   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 16:31 |
| - | 13 | "726599"   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 16:35 |
| - | 24 | "212691"   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 16:34 |

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|---|-----|--------------------------|---|------------------|
| - | 15  | "826791"                 | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 16:34 |
| - | 2   | "9823787"                | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 16:37 |
| - | 14  | "254205"                 | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 17:16 |
| - | 12  | "761841"                 | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 16:40 |
| - | 44  | "519079"                 | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 16:43 |
| - | 18  | "19654737"               | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 16:45 |
| - | 2   | "9629576"                | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 16:45 |
| - | 35  | "0051174"                | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 16:48 |
| - | 2   | "200051174"              | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 16:46 |
| - | 42  | "0101472"                | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 16:48 |
| - | 3   | "9943866"                | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 16:48 |
| - | 221 | macneil.in.              | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 17:16 |
| - | 25  | (macneil near3 john).in. | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 17:17 |

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| - | 8  | US-5876503-\$.DID. OR US-5620524-\$.DID. OR US-5641559-\$.DID. OR US-5738804-\$.DID.  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 17:33 |
| - | 4  | ("5730804" "5786039").pn.   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 17:33 |
| - | 6  | US-4894254-\$.DID. OR US-4822632-\$.DID. OR US-4096315-\$.DID.  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/02 17:38 |
| - | 41 | ("5270267".pn. ((US-3223040-\$.DID. OR US-4793524-\$.DID. OR US-5095938-\$.DID. OR US-5098741-\$.DID. OR US-5195655-\$.DID. OR US-5273851-\$.DID. OR US-5314724-\$.DID. OR US-5356034-\$.DID. OR US-5494712-\$.DID. OR US-5534069-\$.DID. OR US-5593741-\$.DID.) (US-4894254-\$.DID. OR US-4822632-\$.DID. OR US-4096315-\$.DID.) 6028015.pn. (US-5876503-\$.DID. OR US-5620524-\$.DID. OR US-5641559-\$.DID. OR US-5730804-\$.DID.) ) ) 5786039.pn.  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 14:28 |
| - | 29 | ("5270267".pn. ((US-3223040-\$.DID. OR US-4793524-\$.DID. OR US-5095938-\$.DID. OR US-5098741-\$.DID. OR US-5195655-\$.DID. OR US-5273851-\$.DID. OR US-5314724-\$.DID. OR US-5356034-\$.DID. OR US-5494712-\$.DID. OR US-5534069-\$.DID. OR US-5593741-\$.DID.) (US-4894254-\$.DID. OR US-4822632-\$.DID. OR US-4096315-\$.DID.) 6028015.pn. (US-5876503-\$.DID. OR US-5620524-\$.DID. OR US-5641559-\$.DID. OR US-5730804-\$.DID.) ) ) 5786039.pn. ) and (plasma discharge)   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 10:52 |
| - | 13 | ("5270267".pn. ((US-3223040-\$.DID. OR US-4793524-\$.DID. OR US-5095938-\$.DID. OR US-5098741-\$.DID. OR US-5195655-\$.DID. OR US-5273851-\$.DID. OR US-5314724-\$.DID. OR US-5356034-\$.DID. OR US-5494712-\$.DID. OR US-5534069-\$.DID. OR US-5593741-\$.DID.) (US-4894254-\$.DID. OR US-4822632-\$.DID. OR US-4096315-\$.DID.) 6028015.pn. (US-5876503-\$.DID. OR US-5620524-\$.DID. OR US-5641559-\$.DID. OR US-5730804-\$.DID.) ) ) 5786039.pn. ) and (plasma discharge) same (heat\$3 hot)                                    | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 10:19 |
| - | 8  | ("5270267".pn. ((US-3223040-\$.DID. OR US-4793524-\$.DID. OR US-5095938-\$.DID. OR US-5098741-\$.DID. OR US-5195655-\$.DID. OR US-5273851-\$.DID. OR US-5314724-\$.DID. OR US-5356034-\$.DID. OR US-5494712-\$.DID. OR US-5534069-\$.DID. OR US-5593741-\$.DID.) (US-4894254-\$.DID. OR US-4822632-\$.DID. OR US-4096315-\$.DID.) 6028015.pn. (US-5876503-\$.DID. OR US-5620524-\$.DID. OR US-5641559-\$.DID. OR US-5730804-\$.DID.) ) ) 5786039.pn. ) and (plasma discharge) and (heat\$3 hot) near5 (surface substrate)           | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 10:27 |
| - | 4  | ("5270267".pn. ((US-3223040-\$.DID. OR US-4793524-\$.DID. OR US-5095938-\$.DID. OR US-5098741-\$.DID. OR US-5195655-\$.DID. OR US-5273851-\$.DID. OR US-5314724-\$.DID. OR US-5356034-\$.DID. OR US-5494712-\$.DID. OR US-5534069-\$.DID. OR US-5593741-\$.DID.) (US-4894254-\$.DID. OR US-4822632-\$.DID. OR US-4096315-\$.DID.) 6028015.pn. (US-5876503-\$.DID. OR US-5620524-\$.DID. OR US-5641559-\$.DID. OR US-5730804-\$.DID.) ) ) 5786039.pn. ) and (plasma discharge) and (heat\$3 hot) near5 deposit\$8 near5 (film layer) | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 10:34 |

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| - | 11  | ((("5270267".pn. ((US-3223040-\$.DID. OR US-4793524-\$.DID. OR US-5095938-\$.DID. OR US-5098741-\$.DID. OR US-5195655-\$.DID. OR US-5273851-\$.DID. OR US-5314724-\$.DID. OR US-5356034-\$.DID. OR US-5494712-\$.DID. OR US-5534069-\$.DID. OR US-5593741-\$.DID.) (US-4894254-\$.DID. OR US-4822632-\$.DID. OR US-4096315-\$.DID.) 6028015.pn. (US-5876503-\$.DID. OR US-5620524-\$.DID. OR US-5641559-\$.DID. OR US-5730804-\$.DID.) ) ) 5786039.pn. ) and (plasma discharge)) and (CVD (chemical near3 vap\$1or near3 deposition)) and (silane organosilicon)                                 | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 10:38 |
| - | 1   | ((("5270267".pn. ((US-3223040-\$.DID. OR US-4793524-\$.DID. OR US-5095938-\$.DID. OR US-5098741-\$.DID. OR US-5195655-\$.DID. OR US-5273851-\$.DID. OR US-5314724-\$.DID. OR US-5356034-\$.DID. OR US-5494712-\$.DID. OR US-5534069-\$.DID. OR US-5593741-\$.DID.) (US-4894254-\$.DID. OR US-4822632-\$.DID. OR US-4096315-\$.DID.) 6028015.pn. (US-5876503-\$.DID. OR US-5620524-\$.DID. OR US-5641559-\$.DID. OR US-5730804-\$.DID.) ) ) 5786039.pn. ) and (plasma discharge)) and (CVD (chemical near3 vap\$1or near3 deposition)) same (silane organosilicon) same (hydrogen near3 peroxide) | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 10:40 |
| - | 108 | (CVD (chemical near3 vap\$1or near3 deposition)) same (silane organosilicon tetraethoxysilane) near9 (hydrogen near3 peroxide)   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 10:53 |
| - | 92  | ((CVD (chemical near3 vap\$1or near3 deposition)) same (silane organosilicon tetraethoxysilane) near9 (hydrogen near3 peroxide)) and (plasma discharge)  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 10:52 |
| - | 6   | (CVD (chemical near3 vap\$1or near3 deposition)) same (heat\$4 hot) same (silane organosilicon tetraethoxysilane) near9 (hydrogen near3 peroxide)  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 10:53 |
| - | 8   | (CVD (chemical near3 vap\$1or near3 deposition)) same (heat\$4 hot) same (silane organosilicon tetraethoxysilane) same (hydrogen near3 peroxide)   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 11:06 |
| - | 51  | (CVD (chemical near3 vap\$1or near3 deposition)) same (heat\$4 hot anneal\$5) same (silane organosilicon tetraethoxysilane organosilane) same (hydrogen near3 peroxide)  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 11:09 |
| - | 11  | ((CVD (chemical near3 vap\$1or near3 deposition)) same (heat\$4 hot anneal\$5) same (silane organosilicon tetraethoxysilane organosilane) same (hydrogen near3 peroxide)) and (plasma corona discharge) near9 treat\$9   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 11:09 |
| - | 131 | (CVD (chemical near3 vap\$1or near3 deposition)) same (silane organosilicon tetraethoxysilane organosilane) same (hydrogen near3 peroxide)   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 11:09 |
| - | 6   | ((CVD (chemical near3 vap\$1or near3 deposition)) same (silane organosilicon tetraethoxysilane organosilane) same (hydrogen near3 peroxide)) and (plasma corona discharge) near9 treat\$9 same (heat\$4 hot anneal\$5)   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 11:31 |
| - | 5   | "10294311"   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 11:35 |

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| - | 25  | (macneil near3 john).in.   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 11:35 |
| - | 11  | (beekman near3 knut).in.   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 11:35 |
| - | 0   | (wilby near3 anthony near3 paul).in.   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 11:36 |
| - | 0   | (wilby near3 anthony).in.  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 11:36 |
| - | 0   | (wilby near3 paul).in.   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 11:36 |
| - | 32  | ((macneil near3 john).in.) ((beekman near3 knut).in.)  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 11:37 |
| - | 82  | (trikon near3 holdings).as.  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 11:37 |
| - | 102 | ((macneil near3 john).in.) ((beekman near3 knut).in.) ((trikon near3 holdings).as.)  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 11:37 |
| - | 18  | ((macneil near3 john).in.) ((beekman near3 knut).in.) ((trikon near3 holdings).as.) and (plasma corona discharge) and (heat\$3 anneal\$3 hot)  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 12:44 |
| - | 2   | "6544858"  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 12:44 |
| - | 41  | ("5270267".pn. ((US-3223040-\$.DID. OR US-4793524-\$.DID. OR US-5095938-\$.DID. OR US-5098741-\$.DID. OR US-5195655-\$.DID. OR US-5273851-\$.DID. OR US-5314724-\$.DID. OR US-5356034-\$.DID. OR US-5494712-\$.DID. OR US-5534069-\$.DID. OR US-5593741-\$.DID.) (US-4894254-\$.DID. OR US-4822632-\$.DID. OR US-4096315-\$.DID.) 6028015.pn. (US-5876503-\$.DID. OR US-5620524-\$.DID. OR US-5641559-\$.DID. OR US-5730804-\$.DID.) ) ) 5786039.pn. | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 14:28 |

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| - | 5  | ((("5270267".pn. ((US-3223040-\$.DID. OR US-4793524-\$.DID. OR US-5095938-\$.DID. OR US-5098741-\$.DID. OR US-5195655-\$.DID. OR US-5273851-\$.DID. OR US-5314724-\$.DID. OR US-5356034-\$.DID. OR US-5494712-\$.DID. OR US-5534069-\$.DID. OR US-5593741-\$.DID.) (US-4894254-\$.DID. OR US-4822632-\$.DID. OR US-4096315-\$.DID.) 6028015.pn. (US-5876503-\$.DID. OR US-5620524-\$.DID. OR US-5641559-\$.DID. OR US-5730804-\$.DID.) )) 5786039.pn. ) and hydrogen near3 plasma | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 14:29 |
| - | 8  | ((("5270267".pn. ((US-3223040-\$.DID. OR US-4793524-\$.DID. OR US-5095938-\$.DID. OR US-5098741-\$.DID. OR US-5195655-\$.DID. OR US-5273851-\$.DID. OR US-5314724-\$.DID. OR US-5356034-\$.DID. OR US-5494712-\$.DID. OR US-5534069-\$.DID. OR US-5593741-\$.DID.) (US-4894254-\$.DID. OR US-4822632-\$.DID. OR US-4096315-\$.DID.) 6028015.pn. (US-5876503-\$.DID. OR US-5620524-\$.DID. OR US-5641559-\$.DID. OR US-5730804-\$.DID.) )) 5786039.pn. ) and hydrogen near9 plasma | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 14:29 |
| - | 80 | (heat\$3 anneal\$3) near9 hydrogen near9 plasma and crack\$3 and semiconduct\$5   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 14:31 |
| - | 3  | (heat\$3 anneal\$3) same (CVD (chemical near3 vapo\$1r near3 deposit\$4)) same (silane organosilane organosilicon) same hydrogen near9 plasma and crack\$3 and semiconduct\$5   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 14:33 |
| - | 83 | (heat\$3 anneal\$3) same (CVD (chemical near3 vapo\$1r near3 deposit\$4)) same (silane organosilane organosilicon) same hydrogen near9 plasma   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 14:34 |
| - | 8  | (heat\$3 anneal\$3) same (CVD (chemical near3 vapo\$1r near3 deposit\$4)) same (silane organosilane organosilicon) same hydrogen near9 peroxide and hydrogen near9 plasma   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 14:43 |
| - | 44 | (heat\$3 anneal\$3) same (CVD (chemical near3 vapo\$1r near3 deposit\$4)) same (silane organosilane organosilicon) and hydrogen near9 peroxide and hydrogen near9 plasma  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 15:08 |
| - | 4  | (heat\$3 anneal\$3) same (CVD (chemical near3 vapo\$1r near3 deposit\$4)) same (organosilane organosilicon) and hydrogen near9 peroxide and hydrogen near9 plasma   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 15:09 |
| - | 14 | (heat\$3 anneal\$3) same (CVD (chemical near3 vapo\$1r near3 deposit\$4)) same (((methyl ethyl) near3 silane) organosilane organosilicon) and hydrogen near9 peroxide and hydrogen near9 plasma   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 15:22 |
| - | 27 | (heat\$3 anneal\$3) same (CVD (chemical near3 vapo\$1r near3 deposit\$4)) same (((methyl ethyl) near3 silane) organosilane organosilicon) and (carbon methyl) and hydrogen near9 plasma   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 15:23 |
| - | 0  | ((heat\$3 anneal\$3) same (CVD (chemical near3 vapo\$1r near3 deposit\$4)) same (((methyl ethyl) near3 silane) organosilane organosilicon) and (carbon methyl) and hydrogen near9 plasma ) not ((heat\$3 anneal\$3) same (CVD (chemical near3 vapo\$1r near3 deposit\$4)) same (((methyl ethyl) near3 silane) organosilane organosilicon) and carbon and hydrogen near9 plasma )  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 15:23 |

|   |     |   |   |                  |
|---|-----|---|---|------------------|
| - | 27  | (heat\$3 anneal\$3) same (CVD (chemical near3 vapo\$1r near3 deposit\$4)) same (((methyl ethyl) near3 silane) organosilane organosilicon) and carbon and hydrogen near9 plasma          | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 16:44 |
| - | 5   | "6383951"   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 16:39 |
| - | 2   | "6383951" and hydrogen near9 plasma   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 16:40 |
| - | 14  | "5593741" and hydrogen near9 plasma   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 16:41 |
| - | 23  | (heat\$3 anneal\$3) same (CVD (chemical near3 vapo\$1r near3 deposit\$4)) same (((methyl ethyl) near3 silane) organosilane organosilicon) and hydrogen near3 plasma                     | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 16:52 |
| - | 124 | "6054379"   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 16:47 |
| - | 10  | "6054379" and hydrogen near3 plasma   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 16:48 |
| - | 79  | crack\$3 same hydrogen near3 plasma   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 16:50 |
| - | 14  | (crack\$3 same hydrogen near3 plasma) and low near9 dielectric  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 16:49 |
| - | 55  | low near2 "k" near3 dielectric same hydrogen near3 plasma   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 16:52 |
| - | 28  | low near2 "k" near3 dielectric and hydrogen near3 plasma and (CVD (chemical near3 vapo\$1r near3 deposit\$4)) same (((methyl ethyl) near3 silane) organo\$1silane organosilicon)        | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 17:02 |
| - | 24  | hydrogen near3 plasma near9 (treat\$9 heat\$3 anneal\$3) and (CVD (chemical near3 vapo\$1r near3 deposit\$4)) same (((methyl ethyl) near3 silane) organo\$1silane organosilicon)        | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 16:56 |
| - | 237 | hydrogen near3 plasma near9 (treat\$9 heat\$3 anneal\$3) and (CVD (chemical near3 vapo\$1r near3 deposit\$4)) same (((methyl ethyl) near3 silane) silane organo\$1silane organosilicon) | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 16:56 |



|   |     |  |   |                  |
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| - | 25  | hydrogen near3 plasma near9 (treat\$9 heat\$3 anneal\$3) same (CVD (chemical near3 vapo\$1r near3 deposit\$4)) same (((methyl ethyl) near3 silane) silane organo\$1silane organosilicon)   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 17:07 |
| - | 361 | hydrogen near3 plasma same (treat\$9 heat\$3 anneal\$3) and (CVD (chemical near3 vapo\$1r near3 deposit\$4)) same (methyl\$1silane silane organo\$1silane organosilicon)   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 17:02 |
| - | 35  | low near2 "k" near3 dielectric and ( hydrogen near3 plasma same (treat\$9 heat\$3 anneal\$3) and (CVD (chemical near3 vapo\$1r near3 deposit\$4)) same (methyl\$1silane silane organo\$1silane organosilicon) )  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 17:02 |
| - | 1   | hydrogen near3 plasma same flowfill  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 17:07 |
| - | 10  | hydrogen near3 plasma and flowfill   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 17:10 |
| - | 206 | hydrogen near3 plasma same (treat\$9 heat\$3 anneal\$4) same (flowfill "flowfill" (silicon near2 oxide))   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 17:11 |
| - | 221 | hydrogen near3 plasma same (treat\$9 heat\$3 anneal\$4) same (flowfill "flowfill" (silicon near2 oxide) (low near2 "k" near3 dielectric))  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 17:13 |
| - | 210 | ( hydrogen near3 plasma same (treat\$9 heat\$3 anneal\$4) same (flowfill "flowfill" (silicon near2 oxide) (low near2 "k" near3 dielectric))) not (low near2 "k" near3 dielectric and ( hydrogen near3 plasma same (treat\$9 heat\$3 anneal\$3) and (CVD (chemical near3 vapo\$1r near3 deposit\$4)) same (methyl\$1silane silane organo\$1silane organosilicon) ))   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 17:12 |
| - | 243 | hydrogen near3 plasma same (treat\$9 heat\$3 anneal\$3) and (CVD (chemical near3 vapo\$1r near3 deposit\$4)) same (methyl\$1silane silane organo\$1silane organosilicon) and (flowfill "flowfill" (silicon near2 oxide) (low near2 "k" near3 dielectric))  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 17:16 |
| - | 35  | hydrogen near3 plasma same (treat\$9 heat\$3 anneal\$3) and (CVD (chemical near3 vapo\$1r near3 deposit\$4)) same (methyl\$1silane silane organo\$1silane organosilicon) and (flowfill "flowfill" (low near2 "k" near3 dielectric))  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 17:15 |
| - | 0   | ( hydrogen near3 plasma same (treat\$9 heat\$3 anneal\$3) and (CVD (chemical near3 vapo\$1r near3 deposit\$4)) same (methyl\$1silane silane organo\$1silane organosilicon) and (flowfill "flowfill" (low near2 "k" near3 dielectric))) not (low near2 "k" near3 dielectric and ( hydrogen near3 plasma same (treat\$9 heat\$3 anneal\$3) and (CVD (chemical near3 vapo\$1r near3 deposit\$4)) same (methyl\$1silane silane organo\$1silane organosilicon) )) | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 17:15 |
| - | 996 | hydrogen near3 plasma same (treat\$9 heat\$3 anneal\$3) and (CVD (chemical near3 vapo\$1r near3 deposit\$4)) same (methyl\$1silane silane organo\$1silane organosilicon flowfill "flowfill" (silicon near2 oxide) (low near2 "k" near3 dielectric))  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 17:17 |

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| - | 109  | hydrogen near3 plasma same (treat\$9 heat\$3 anneal\$3) same (CVD (chemical near3 vapo\$1r near3 deposit\$4)) same (methyl\$1silane silane organo\$1silane organosilicon flowfill "flowfill" (silicon near2 oxide) (low near2 "k" near3 dielectric))  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 17:17 |
| - | 100  | ( hydrogen near3 plasma same (treat\$9 heat\$3 anneal\$3) same (CVD (chemical near3 vapo\$1r near3 deposit\$4)) same (methyl\$1silane silane organo\$1silane organosilicon flowfill "flowfill" (silicon near2 oxide) (low near2 "k" near3 dielectric))) not (low near2 "k" near3 dielectric and ( hydrogen near3 plasma same (treat\$9 heat\$3 anneal\$3) and (CVD (chemical near3 vapo\$1r near3 deposit\$4)) same (methyl\$1silane silane organo\$1silane organosilicon) )) | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 19:09 |
| - | 2314 | teos near3 tetraethoxy\$1silane   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 18:03 |
| - | 146  | (teos near3 tetraethoxy\$1silane).ab.   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 18:03 |
| - | 20   | "6063654"   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/03 19:09 |